

# A Modelling Framework for Understanding Screen-Printing of Copper Pastes in Solar Cell Metallisation

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# DEPARTMENT OF MATERIALS

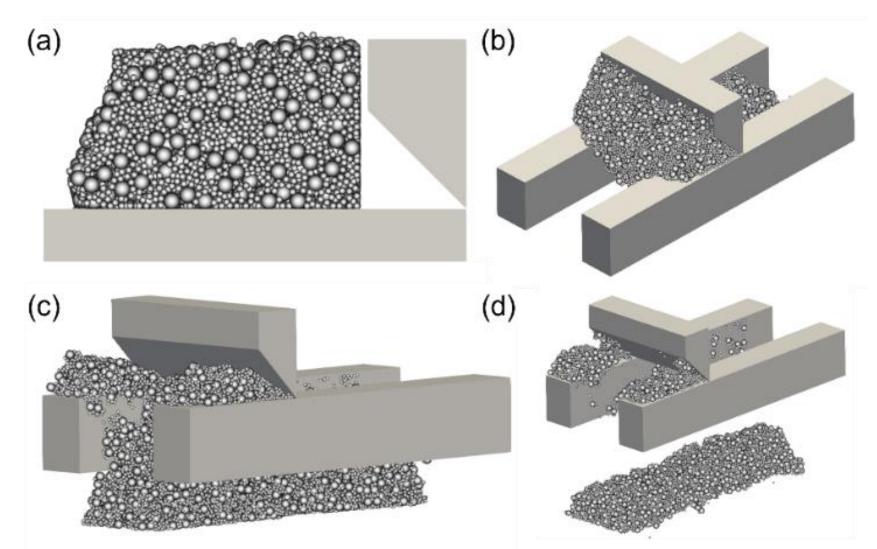
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## Introduction

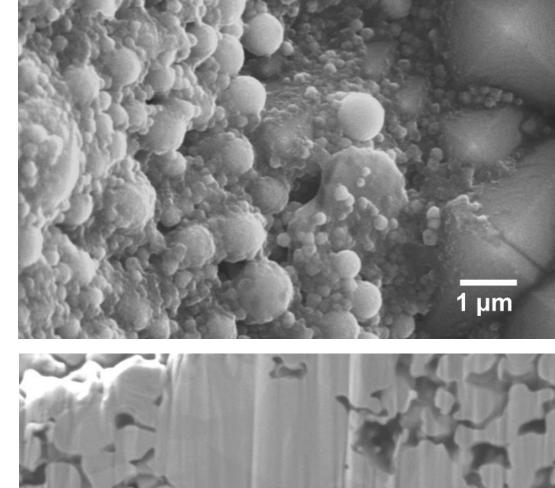
- Copper is a promising replacement for unsustainable silver metallisation.
- Screen-printed copper pastes suffer from limited conductivity.
- Therefore, we developed a modelling approach to predict and improve the conductivity of screen-printed copper pastes.

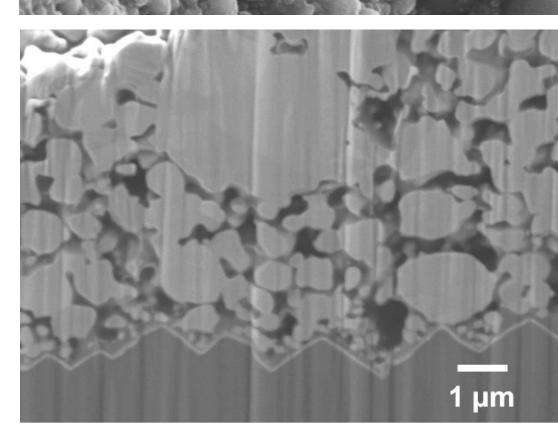
#### Methods

- DEM simulation of Cu screenprinting (deposition → squeegee → lift-off → relaxation) using LIGGGHTS.
  - Particle interactions modelled with cohesive forces calibrated to Cu paste morphology.

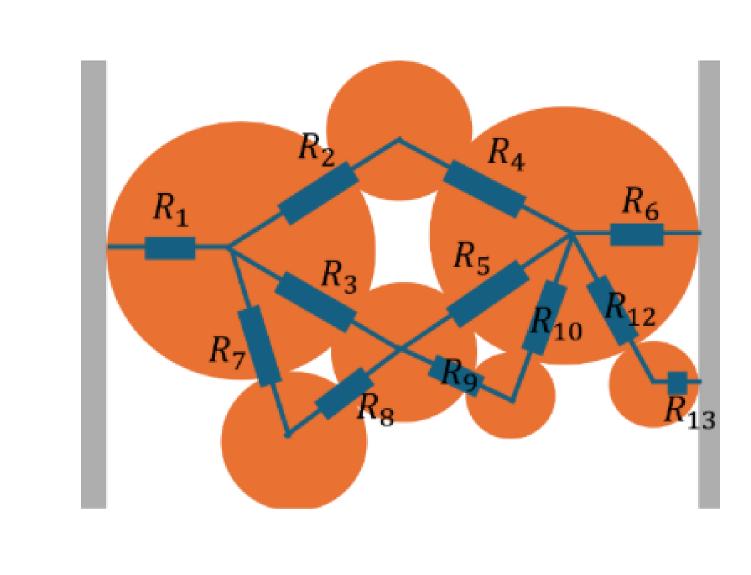


- SEM imaging
- SEM used to gain insight into experimental morphology.



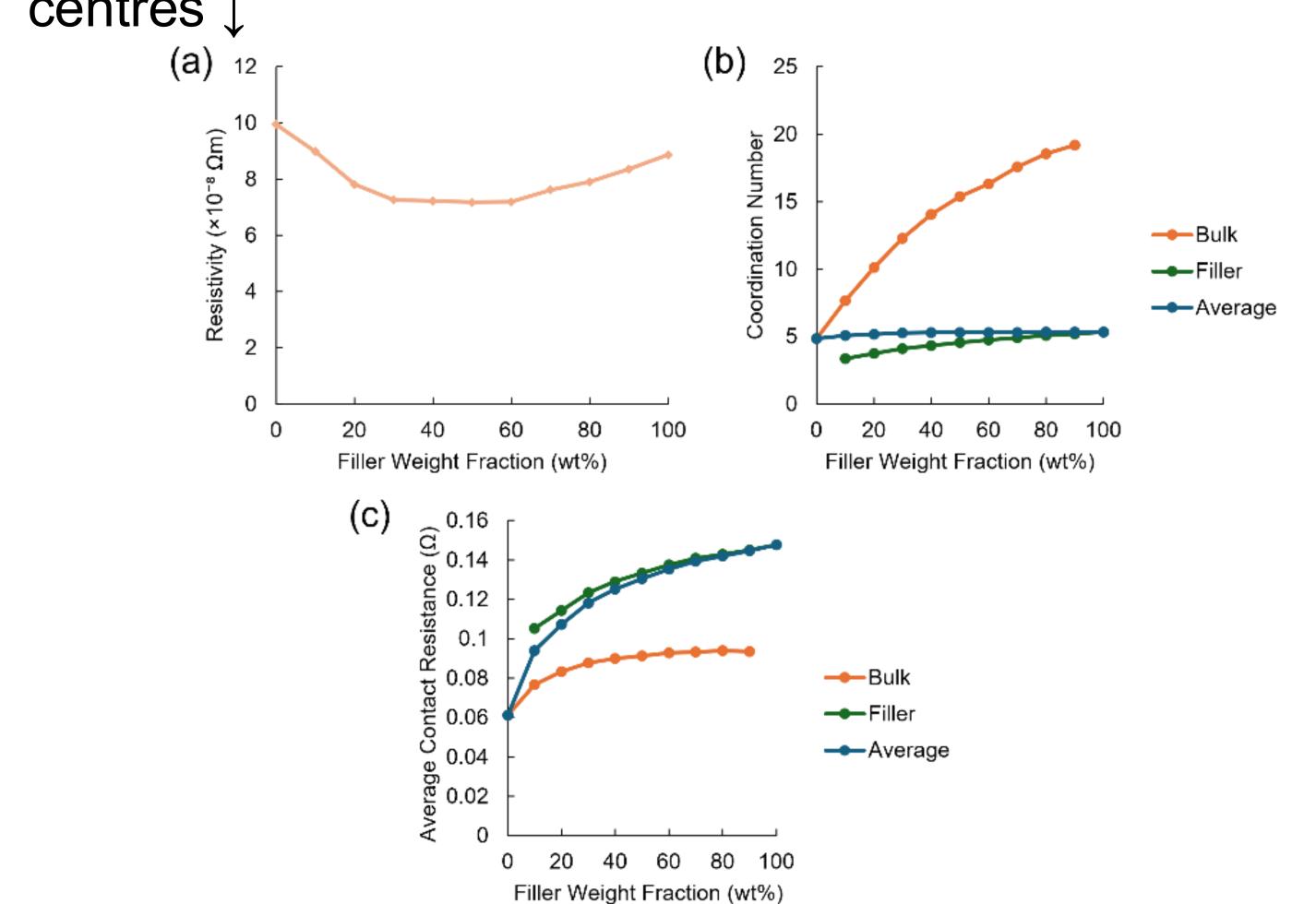


 Resistive network model built from geometric solution [1]; resistivity calculated via NetworkX (Kirchhoff's laws).



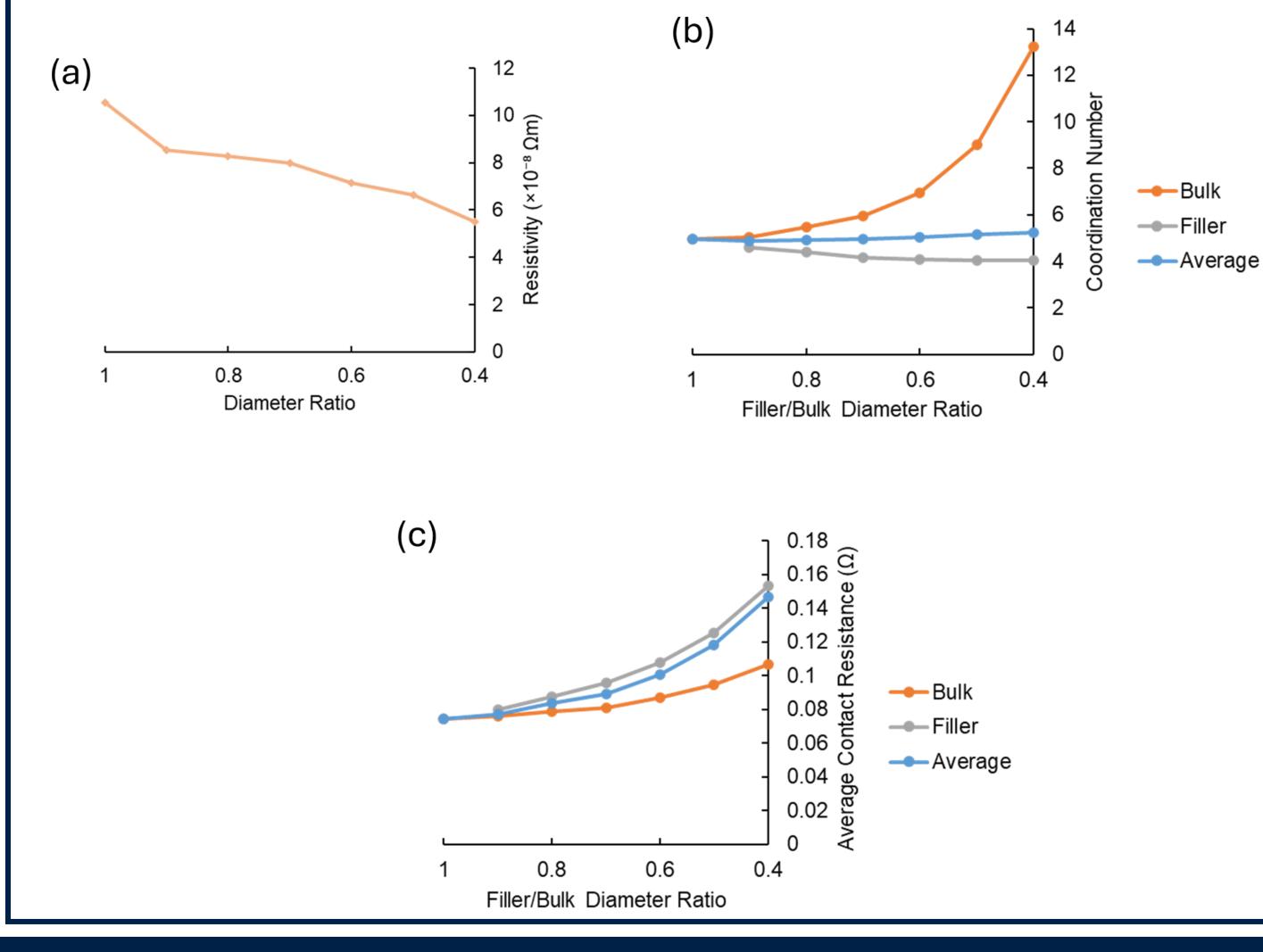
## The Effect of Particle Distribution

- Bimodal Cu mixtures with varied filler size and fraction.
- Smaller fillers bridge bulk particles, consistent with SEM.
- Bulk particles provide conductive hubs; fillers improve connectivity.
- Minimum resistivity at 40–60 wt% filler, matches experimental findings [2].
- Filler addition → coordinated bulk particles ↑ → enables parallel current pathways.
- Excess filler → contact resistance ↑ → bulk conductive centres ↓



# The Effect of Particle Sizes

- Filler diameter varied: 0.4–1 μm (bulk = 1 μm, 30 wt% filler).
- Resistivity ↓ with decreasing diameter ratio.
- Coordination number (N<sub>c</sub>) roughly constant overall, but doubles for bulk particles as d<sub>r</sub> ↓
- Smaller fillers → packing density ↑ → connectivity ↑ → resistivity↓



# Conclusions

- DEM + resistive network model successfully predicts Cu paste resistivity.
- Higher coordination  $\rightarrow$  more parallel paths  $\rightarrow$  lower resistance.
- Enables fast, low-cost optimisation of sustainable Cu metallisation.





